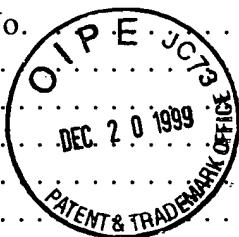


#6/Amndt B
12/28/99
C. McKinney

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/059,644
Filing Date April 13, 1998
Inventor Pai-Hung Pan
Assignee Micron Technology, Inc.
Group Art Unit 2822
Examiner M. Trinh
Attorney's Docket No. MI22-898
Title: Semiconductor Processing Methods Of Forming A Conductive Gate and Line



RESPONSE TO SEPTEMBER 16, 1999 OFFICE ACTION

To: Assistant Commissioner for Patents
Washington, D.C. 20231

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
Wells, St. John, Roberts, Gregory & Matkin P.S.
601 W. First Avenue, Suite 1300
Spokane, WA 99201-3828

Sir:

Responsive to the Office Action dated September 16, 1999,
Applicant amends and remarks as follows [unless otherwise indicated,
deletions are bracketed, additions are underlined]:

AMENDMENTS

In the Claims

In Claim 43, at line 2, insert --layer-- after the phrase "overlying metal".

In Claim 46, at line 1, replace "said" with --the--.

In Claim 51, at line 4, replace "anisotropically" with
--anisotropically--.

B